

ABSTRACT

Disclosed are a substrate bearing device and a substrate processing apparatus in relation to the field of semiconductor equipment. The substrate bearing device comprises: a connecting member, including a connecting main body extending in the vertical direction; a bearing member, connected to the connecting member, extending in the horizontal direction, and bearing a plurality of substrates in a manner that the plurality of substrates are parallel to the vertical direction, wherein the plurality of substrates include a first substrate adjacent to a major surface of the connecting member; the connecting member further includes a flow rectifying portion, a major surface of the flow rectifying portion is flush with a major surface of the connecting main body, and the flow rectifying portion is configured such that when the bearing member bears the substrates, the orthographic projection of the first substrate on the flow rectifying portion is located inside the flow rectifying portion. The present invention greatly improves the flow field on the side of the first substrate close to the flow rectifying portion, thereby enhancing the cleaning effect of the first substrate. The major surface of the flow rectifying portion is flush with the major surface of the connecting member, so that the flow field is more stable during the cleaning process.